Homework Assignments

**Homework 01:** Assigned June 12, 2010 - Due June 26, 2010  
**Topic:** Process Development-Device Physics-Scaling  
**Chapters 2-5 (Field Effect Devices):** 2.1, 2.3, 3.4, 4.10, 4.11, 5.1(a-e), 5.3  
**Comment:** Typo in 3.4g repeats “and V_D”

**Project Proposal (1-2 Pages, Single Spaced):** Due July 3, 2010

**Homework 02:** Assigned July 10, 2010 - Due July 24, 2010  
**Topic:** Evolution of the MOSFET Device-Thin Oxide Films-High-k Dielectrics

**Homework 03:** Assigned July 24, 2010 - Due August 7, 2010  
**Topic:** Deep Submicron MOSFET- Shallow Trench Isolation and SOI-Metal Interconnects

**Term Paper (10-20 Page Literature Review, Properly Referenced):** Due August 7, 2010